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(54) RESIST COMPOSITION AND PATTERNING PROCESS

- (71) Applicant: Shin-Etsu Chemical Co., Ltd., Tokyo
- (72) Inventors: Jun Hatakeyama, Joetsu (JP); Masaki Ohashi, Joetsu (JP)
- (73) Assignee: SHIN-ETSU CHEMICAL CO., LTD., Tokyo (JP)
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Primary Examiner — John S Chu (74) Attorney, Agent, or Firm — Westerman, Hattori, Daniels & Adrian, LLP

(57) ABSTRACT

A resist composition comprising a base polymer and a biguanide salt compound offers a high dissolution contrast, minimal LWR, and dimensional stability on PPD.

16 Claims, No Drawings